

Special Issue

Reliability and Engineering Applications (Volume II)

Message from the Guest Editors

This Special Issue, "Reliability and Engineering Applications (Volume II)", aims to provide insights into recently developed advanced reliable processes, techniques, and applications that address challenging engineering problems. Unique and novel manufacturing processes, modeling, and numerical methods for any industrial application are of special interest.

Guest Editors

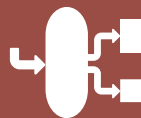
Dr. Hongyun So

Dr. Jong-Won Park

Dr. Sunghan Kim

Deadline for manuscript submissions

closed (5 September 2025)



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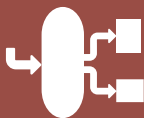


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Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
processes@mdpi.com

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Prof. Dr. Giancarlo Cravotto

Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

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